

# COMPARISON OF FOUR DATA ANALYSIS SOFTWARE FOR COMBINED X-RAY REFLECTIVITY AND GRAZING INCIDENCE X-RAY FLUORESCENCE MEASUREMENTS

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# Ceatech OUTLINE

- GiXRF XRR combined analysis
- Comparison of 4 data analysis software
  - GIMPY, JGIXA, MAUD, MEDEPY
  - Main features
  - Key differences
    - Material Database
    - Sample definition
    - Instrumental function
  - XRR simulation
  - GiXRF simulation
  - Fitting capabilities
- Summary and outlook



# NON-DESTRUCTIVE ELEMENTAL DEPTH PROFILING WITH X-RAYS



Analysis of (ultra)thin layered films for advanced applications (micro/nano electronics, memory, photonics, PV, ...)

### Analytical challenges

- Reduced material quantities ⇒ limits of detection
- Material properties different from bulk ⇒ non-existent standards
- Analysis of interfaces and buried layers 

   ⇒ destructive or indirect methods
- Accuracy, standardization

### Need for non-destructive depth-profiling method

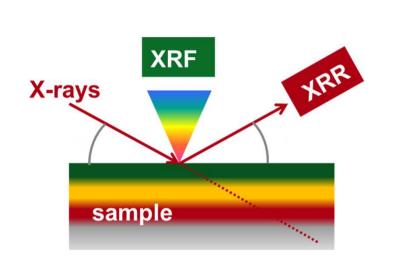
- Avoid artifacts (preferential sputtering, atom mixing, implantation)
- Limited (if any) degradation of the sample
- On beamlines, in the Labs, ... in R&D cleanrooms, in industry

### Combined GIXRF/XRR ?



### **GIXRF+XRR ANALYSIS**





XRR : FT(electron density),  $\theta \ge \theta_c$ 

GiXRF: FT(atomic density),  $\theta \leq \theta_c$ 

Combined XRR-GiXRF: depth-dependent characterization

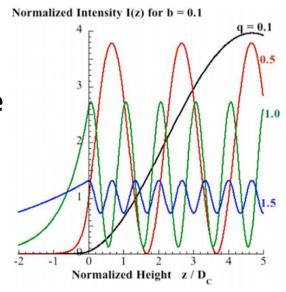
### **GIXRF+XRR DEPTH PROFILING**



$$I_{x}(\theta, \alpha, E_{0}) = I_{0} G(\theta, \alpha, E_{0}) \sum_{j=1}^{n} S_{x,E_{0}} \exp \left[ -\sum_{n=1}^{j-1} (\mu / \rho)_{n,E} \rho_{n} d_{n} \right]$$

$$\int_{C_{j}}^{d_{j}} C_{j}(z) A^{XSW}(E_{j}, \theta, z) \exp \left[-(\mu/\rho)_{j,E} \rho_{j} z\right] dz$$
Propagation of GiXRF-XRR requires:

- Fundamental parameters (timized protocols absorption coefficients), densities, XSW enhancement Data reduction software
- Thicknesses of layers to fit
- Quantification of the XRF dose (geometrical factors)
- Same model for XRR and GiXRF: increase the level of information. Add constraints & reduce uncertainties



SOFTWARE	AUTHORS	KEY FEATURES	REFERENCES
GIMPY Grazing Incidence Material analysis with Python	G. Pepponi, F. Brigidi	XRR, XRF, GiXRF Integrated intensities	• TXRF'15 : Frid. 10.10 am
JGIXA	D. Ingerle	XRR, GiXRF Integrated intensities	<ul> <li>Spectrochimica Acta Part B 99 (2014) 121–128</li> <li>TXRF'15: Wed. 3.30 pm</li> </ul>
MAUD  Material Analysis  Using Diffraction	L. Lutterotti	XRR, XRF, GiXRF, XRD Full spectrum	<ul> <li>Nuclear Inst. and Methods in Physics Research, B, 268, 334- 340, 2010</li> <li>http://maud.radiographema.c om/</li> </ul>
MEDEPY Material Elemental DEpth profiling using PYthon	B. Detlefs, G. Picot, E. Nolot, H. Rotella	XRR, GIXRF, XSW Integrated intensities	• TXRF'15 : Frid. 9.30 am

# Ceatech OVERVIEW

### Common points

- XRR based on Parrat formalism (L. G. Parratt, Phys. Rev., vol. 95, no. 2, p.359, 1954)
- GiXRF based on De Boer formalism (D. K. G. de Boer, http://dx.doi.org/10.1103/PhysRevB.44.498)

### Key differences

- XRF : full spectrum vs integrated intensity
  - Additional SW (e.g PyMCA) is required to extract the integrated XRF intensities for each angle / each XRF line
- Material database
- Sample definition
- Instrumental function
- Other features (simulation & fitting modules)

## Ceatech MATERIAL DATABASE



The values of parameters such as:

Fluorescence yield, Atomic scattering factors, Photoelectric, elastic and inelastic scattering cross sections ...

may not be constant over publications / material database

### **SOFTWARE**

### MATERIAL DATABASE

### **GIMPY, JGIXA, MAUD**

https://data-minalab.fbk.eu/txrf/xraydata/element/

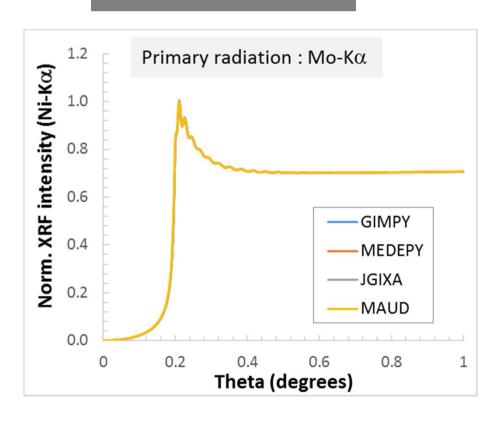
### **MEDEPY**

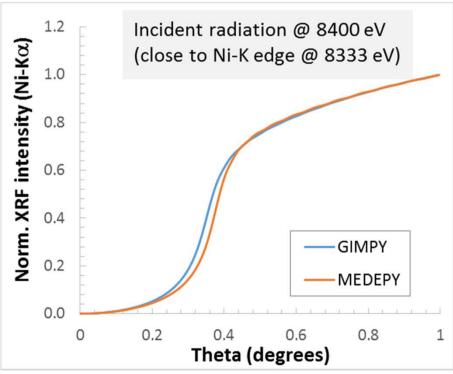
- User defined
- Xray Lib (http://ftp.esrf.eu/pub/scisoft/xraylib/readme.html)

NiO<sub>2</sub> (5nm, d=6.0g/cc)

Ni (50 nm, d=8.9 g/cc)

Si (sub, d=2.33 g/cc)





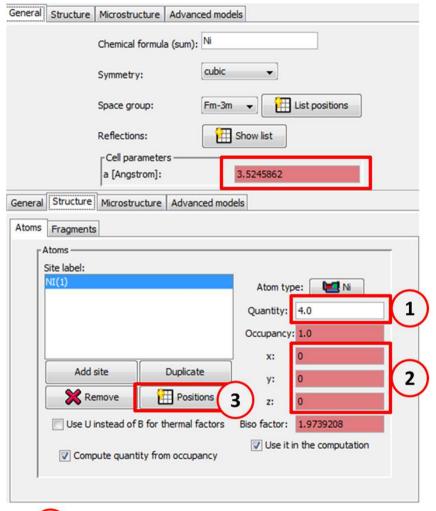
# Ceatech SAMPLE DEFINITION

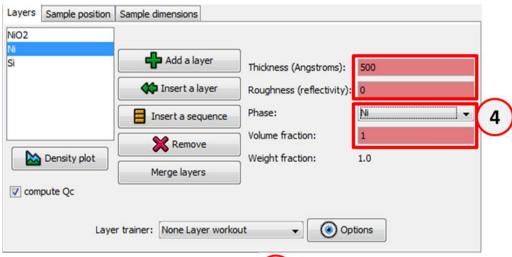


SOFTWARE	PARAMETERS	REMARKS
GIMPY, JGIXA	Thickness Roughness Mass density Stoichiometry	No correlation between mass density and stoichiometry
MAUD	Thickness Roughness Phase Stoichiometry	<ul> <li>XRD-based definition of the sample structure</li> <li>Compatible with XRR-GiXRF-XRD combined analysis</li> </ul>
MEDEPY	Thickness Roughness Mass density or atomic density Stoichiometry	<ul> <li>Mass density and stoichiometry are correlated</li> <li>GENX-based definition</li> </ul>

# ceatech SAMPLE DEFINITION (MAUD)

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Density / Stoechio described by phase

- Atoms per cell
- Position of the first atom
- Position of all the atoms

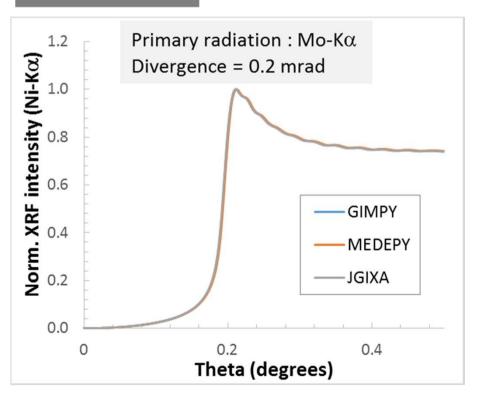
# Ceatech INSTRUMENTAL FUNCTION

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### **XRR**

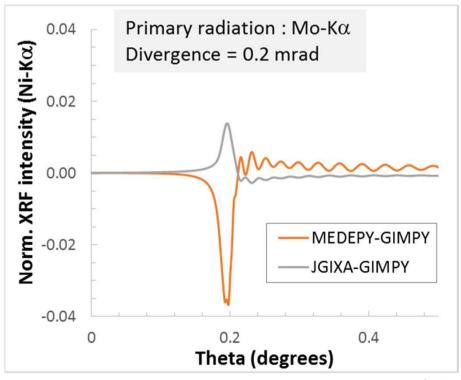
Divergence ~ overall resolution

 $NiO_2$  (5nm, d=6.0g/cc) Ni (50 nm, d=8.9 g/cc) Si (sub, d=2.33 g/cc)



### **GiXRF**

- Divergence (convolution ~ approximation ...)
- Geometrical correction

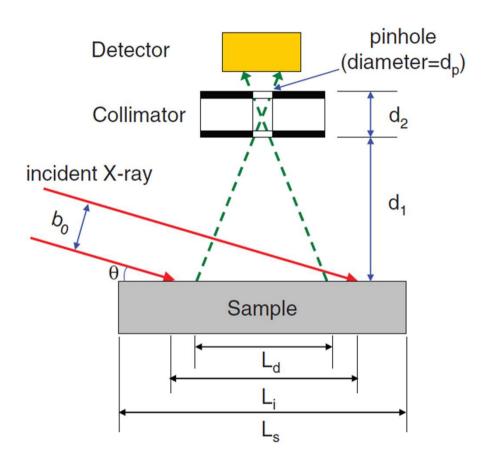


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### **Geometrical correction**

- Acceptance function (detected area corrected by solid angle of detection)
- Spatial intensity distribution of the incident beam (e.g gaussian)

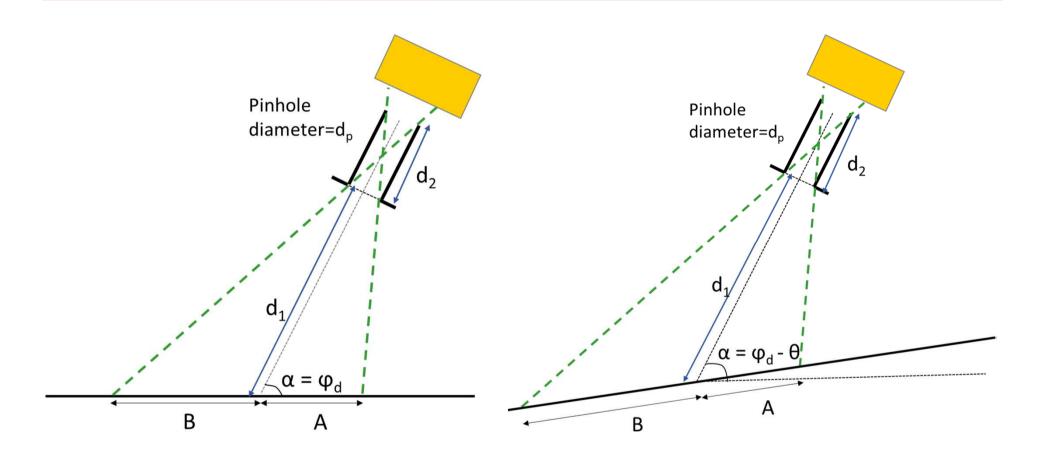


theta-theta configuration Detector angle =  $90^{\circ}$ 

W. Li et al, Review of Scientific Instruments **83**, 053114 (2012)

# Ceatech GEOMETRICAL CORRECTION





theta-theta configuration Detector angle ≠ 90°

theta-2theta configuration **Detector angle** ≠ 90°

# Ceatech ACCEPTANCE FUNCTION

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### **JGIXA**

- Rectangular function (width  $L_d$ )
- Parameter =  $L_d$
- $1/\cos(\theta)$  correction for  $\theta$ -2 $\theta$  geometry

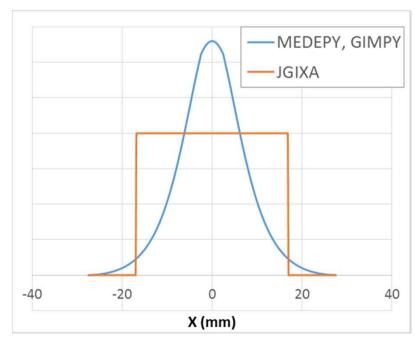
G(
$$\theta$$
)  $\propto \frac{\Delta\Omega}{4\pi} \int_{-L_s/2}^{L_s/2} g(\theta, t) \prod_{L_d} (t) dt$ 

Spatial intensity distribution of the incident beam

Rectangular function of the detectable area with a width of Ld

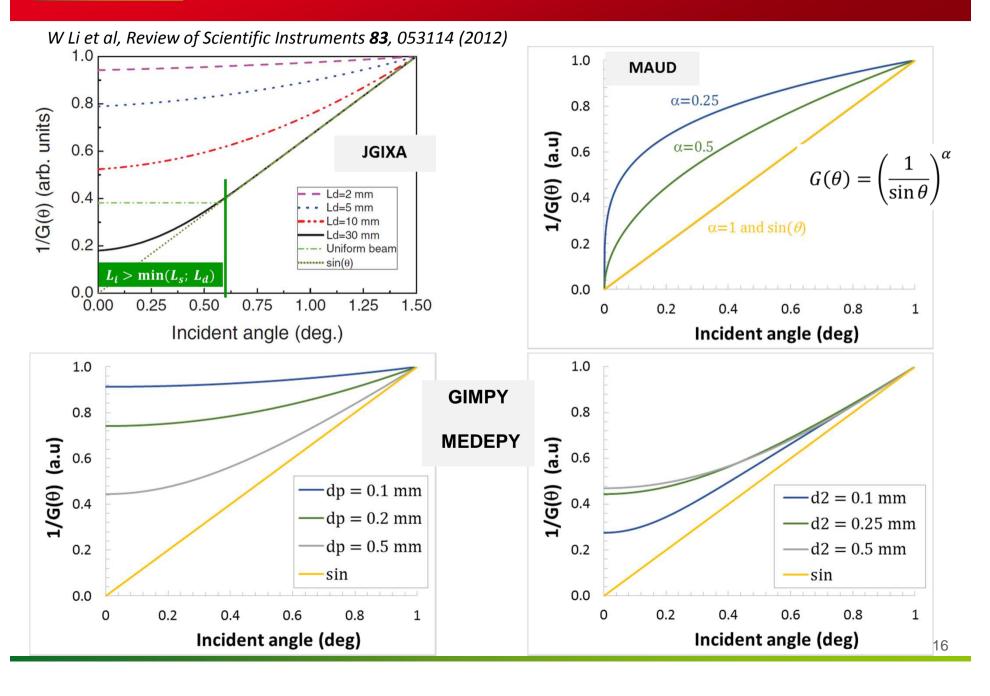
### **GIMPY, MEDEPY**

- Parameters  $d_1$ ,  $d_2$ ,  $d_p$
- Heumans lambda function (solid angle of detection)
- Independent (resp. dependent) of theta in  $\theta$ - $\theta$  (resp.  $\theta$ - $2\theta$ ) geometry



# Ceatech GEOMETRICAL CORRECTION







# **SIMULATION**



NiO<sub>2</sub> (5nm, d=6.0g/cc)

Ni (50 nm, d=8.9 g/cc)

Si (sub, d=2.33 g/cc)

### **XRR** simulation

### **GiXRF** simulation

For NiO<sub>2</sub>/Ni/Si sub case study where thicknesses, densities and roughness were varied and when using the same database :

- the simulated XRR data obtained with the 4 different software were found almost perfectly identical
- the simulated GiXRF data obtained with the 4 different software on a « perfect » tool (no divergence, no instrumental function) were found almost perfectly identical

Impact of the instrumental function (overall divergence) is almost perfectly identical for the different software

- Limited discrepancy induced by divergence
- Significant impact of the geometrical correction
- Only GIMPY includes secondary fluorescence...



# FITTING CAPABILITIES



SOFTWARE	CAPABILITIES	REMARKS
GIMPY		Fitting module under development
JGIXA	Combined fitting of XRR and GiXRF datasets acquired at the same energy	<ul><li>Fast and user friendly</li><li>Monochromatic primary radiation</li></ul>
MAUD	<ul> <li>Unique capability for XRR- XRD-GiXRF combined analysis</li> <li>Stoichiometry</li> </ul>	<ul> <li>Full spectrum only</li> <li>GiXRF instrumental function to be corrected!</li> <li>Monochromatic and polychromatic primary radiation</li> </ul>
MEDEPY	<ul> <li>Combined fitting of various XRR and GiXRF datasets acquired at various energies</li> <li>Stoichiometry</li> </ul>	<ul> <li>Monochromatic primary radiation</li> <li>Still under optimization (definition of FOM for combined analysis)</li> </ul>

# **SUMMARY AND OUTLOOK**



- Analysis of (ultra)thin layered films for advanced applications (micro/nano electronics, memory, photonics, PV, ...)
- Need for combined GIXRF/XRR as a non-destructive depth-profiling method
  - On beamlines, in the Labs, ... in R&D cleanrooms, in industry
- GiXRF/XRR software
  - 4 powerful software have been tested
- Need for standardization (reduced instrumental function ...) in order to meet the needs for depth-dependent quantitative analysis in Labs, R&D facilities and industry

# Thank you for your attention!